Korean International Semiconductor Conference & Exhibition
on Manufacturing Technology 2025

KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[TuB1] Advanced Etchg I

Session Date	November 11 (Tue.), 2025
Session Time	13:00-14:40
Session Room	Room B (Grand Ballroom 1, 2F)

[TuB1-1] [Plenary] **13:00-13:45**

Etch Innovation for 3D Electronic Devices

Thorsten Lill and Harmeet Singh (Lam Research, USA)

[TuB1-2] [Invited] **13:45-14:15**

Nonhalogen Etching for Hard-to-Etch Materials: A Concept Developed from Wet-Like Plasma Technology for Semiconductor Device Fabrication

Thi-Thuy-Nga Nguyen (Nagoya Univ., Japan)

[TuB1-3] [Invited] **14:15-14:40**

K-PIC: A Particle-in-Cell Plasma Simulation for RF Capacitively Coupled Plasmas

Hae June Lee (Pusan Nat'l Univ., Korea)